

Figure 1
(prior art)

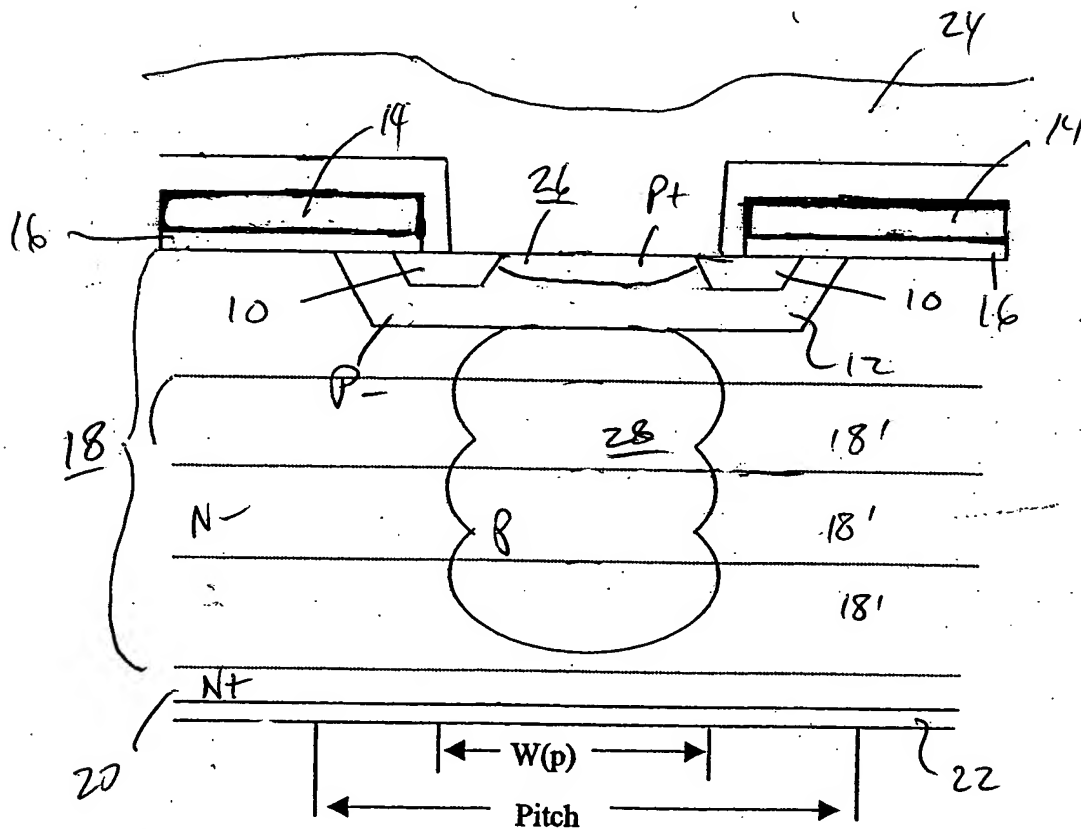


Figure 2
(prior art)

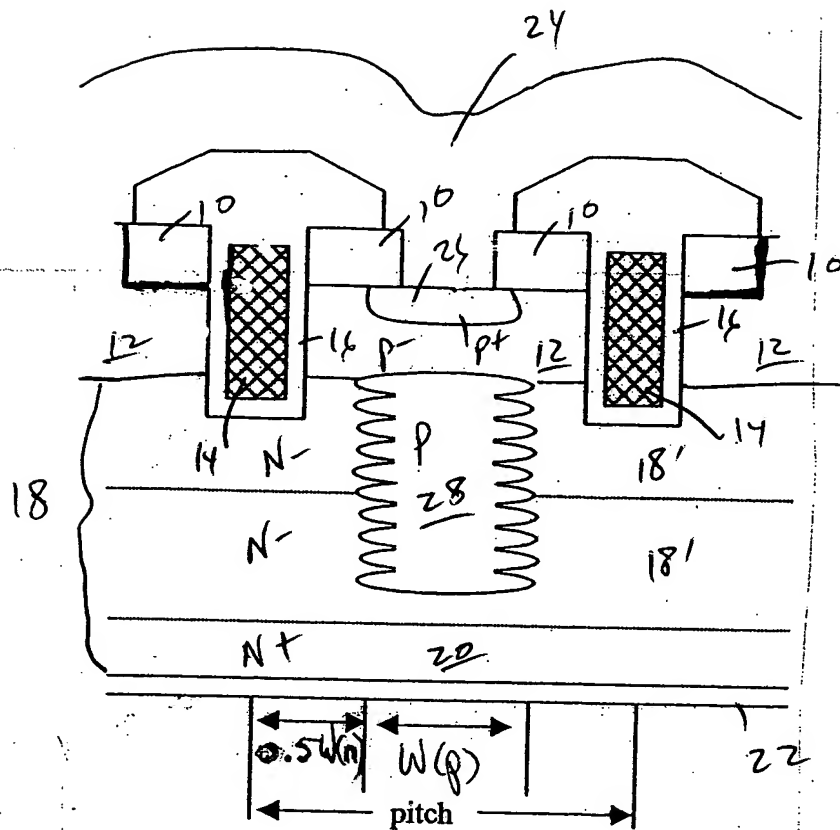


Figure 3
(prior art)

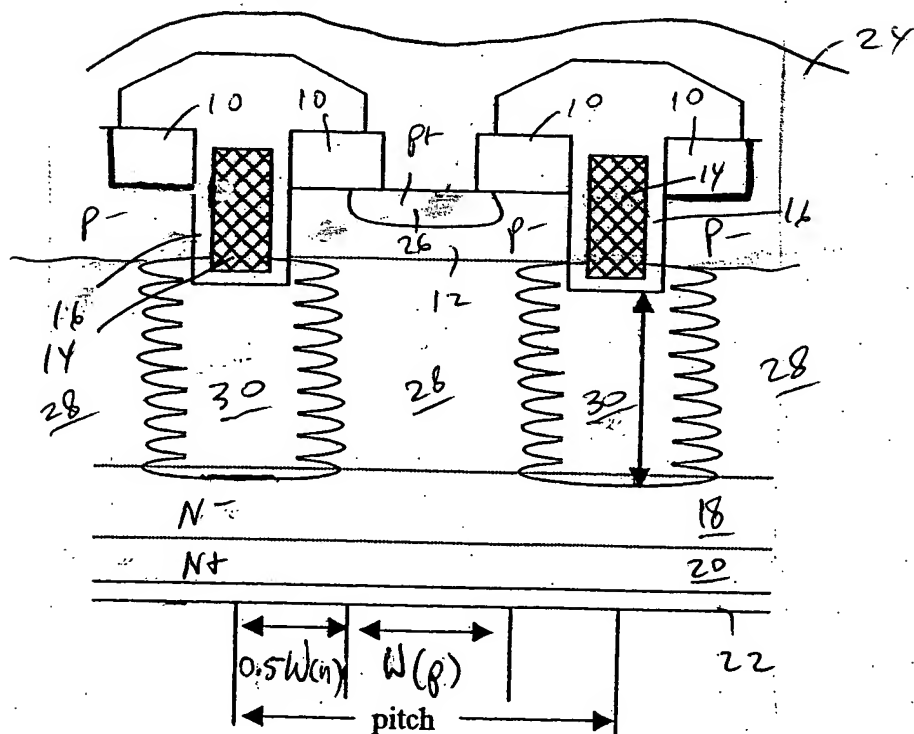


Figure 4

Hand-drawn cross-sectional diagram of a trench structure. The diagram shows a central trench flanked by two side walls. The top layer is labeled "Photoresist" and the middle layer is labeled "Trench Hard Mask". Dimensions are indicated by numbers and arrows:

- Top layer (Photoresist) thickness: 10 (left), 10 (center), 10 (right).
- Side wall height: 12 (left), 12 (right).
- Trench depth: 28 (left), 28 (center), 28 (right).
- Trench width: 40 (left), 40 (center), 40 (right).
- Bottom layer thickness: 30 (left), 30 (center), 30 (right).
- Bottom layer height: 18 (right).
- Bottom layer width: 20 (bottom right).

Figure 5B

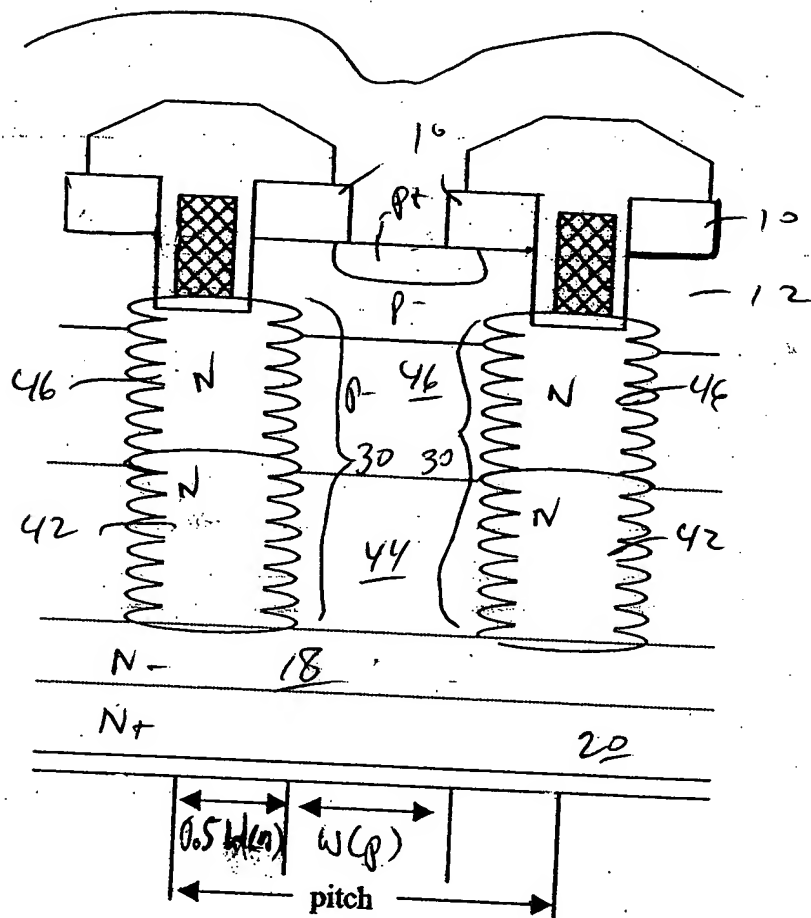


Figure 6